REMARKS

Favorable reconsideration is respectfully requested.

The claims are 1-12.

With regard to Official Action paragraph 1, the suggested change has been made.

With regard to Official Action paragraph 3, claim 3 has now been made dependent on claim 2 so that there is sufficient antecedent basis.

With regard to Official Action paragraph 4, claim 5 has been clarified by the above amendment.

With regard to the rejection on double patenting in Official Action paragraph 6, there is submitted herewith a Terminal Disclaimer disclaiming the terminal portion of any patent maturing from the present application which extends beyond the expiration date of commonly assigned US 6,387,587.

No further issues remaining, allowance of this application is respectfully requested.

If the Examiner has any comments or proposals for expediting prosecution, please contact undersigned at the telephone number below.

Respectfully submitted,

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Version with Markings to Show Changes Made

WHAT IS CLAIMED IS:

1. A positive-working chemical-amplification photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) 100 parts by weight of a combination of a first copolymeric resin consisting of from 62 to 68% by moles of monomeric units (a) hydroxyl group containing styrene units, from 15 to 25% by moles of monomeric units (b) styrene units and from 12 to 18% by moles of monomeric units (c) acrylate or methacrylate ester units each having a solubility-reducing group capable of being eliminated in the presence of acid and a second copolymeric resin consisting of from 62 to 68% by moles of the monomeric units (a), from 25 to 35% by moles of the monomeric units (b) and from 2 to 8% by moles of the monomeric units (c);

(B) from 1 to 20 parts by weight of a radiation-sensitive acid-generating agent which is an onium salt containing a fluoroalkyl sulfonate ion having 3 to 10 carbon atoms as the anion.

2. The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the solubility-reducing group capable of being eliminated in the presence of an acid is selected from the group consisting of tertiary alkyl groups, 1-alkoxyalkyl groups and acetal groups.

3. (amended) The positive-working chemical-amplification photoresist composition as claimed in claim ~~1~~ 2 in which the tertiary alkyl group is tert-butyl group.

4. (amended) The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the

component (B) is an onium salt compound containing a nonafluorobutane sulfonate ion ~~an~~ as the anion.

5. (amended) The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which ~~the~~ each of the first and second copolymeric resins ~~as the component (A)~~ has a weight-average molecular weight in the range from 3000 to 30000.

6. The positive-working chemical-amplification photoresist composition as claimed in claim 1 which further comprises:

(C) an amine compound selected from the group consisting of secondary amines and tertiary amines in an amount in the range from 0.001 to 10 parts by weight per 100 parts by weight of the component (A).

7. The positive-working chemical-amplification photoresist composition as claimed in claim 1 which further comprises: (D) a carboxylic acid compound in an amount in the range from 0.001 to 10 parts by weight per 100 parts by weight of the component (A).

8. The positive-working chemical-amplification photoresist composition as claimed in claim 1 which further comprises dimethylacetamide in an amount in the range from 0.1 to 5.0% by weight based on the amount of the component (A).

9. The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the hydroxyl group-containing styrene unit as the monomeric unit (a) in the component (A) is a hydroxystyrene unit.